

- (currently amended)
10. (Original) The lower shield of claim 9, wherein the mounting center portion further comprises a plurality of mounting holes and lift pin holes disposed therethrough.
11. (Original) The lower shield of claim 9 further comprising an aperture extending through the center portion concentrically disposed inward of the bore.
12. (Currently amended) A replaceable process kit for a processing chamber, the kit comprising:
- a conductive, annular upper shield having a cylindrical portion terminating in an end having circumscribing a first diameter; and
 - a conductive lower shield comprising:
 - a center portion having a first surface facing the end circumscribing the first diameter and a second surface opposite the first surface; ^{and}
 - a lip projecting from the first surface ~~of a portion of the center portion~~ and having circumscribing a diameter greater than a the first diameter ~~of the end of the cylindrical portion of the shield~~, the lip configured to maintain a spaced-apart relation from the ~~substrate support member~~ annular upper shield, and wherein the annular upper shield and the conductive lower shield are adapted to be disposed in the spaced-apart relation wherein the annular upper shield does not intersect a plane defined by the first surface.
13. (Original) The kit of claim 12, wherein the lower shield further comprises:
- a bore disposed at least partially through the center portion and having a sidewall; and
 - a groove disposed in the sidewall.
14. (Original) The kit of claim 12, wherein the center portion further comprises a plurality of mounting holes and a plurality of lift pin holes disposed therethrough.